

In the Specification

The paragraph beginning at line 9 on page 6 has been amended as shown below:

Figure 1 shows in a general illustration an EUV projection lighting installation having a complete EUV lighting system comprising a light source 1, for example a laser-plasma, plasma or pinch-plasma source or else another EUV light source, and a projection objective 2 25 illustrated merely in principle. Apart from the light source 1, there are arranged in the lighting system a collector mirror 2 which, for example, can comprise a plurality of shells arranged in one another, a planar mirror 3 or reflective spectral filter, an aperture stop 4 with an image of the light source (not designated), a first optical element 5 having a large number of facet mirrors 6 (see figures 2 and 3), a second optical element 7 arranged thereafter and having a large number of grid elements 8 in the form of facet mirrors, and two projection mirrors 9a and 9b. The projection mirrors 9a and 9b are used to project the facet mirrors 8 of the second optical element 7 into an entry pupil of the projection objective 2 25. The reticle 12 can be moved in the y direction as a scanning system. The reticle plane 11 also simultaneously constitutes the object plane.

The paragraph beginning at line 14 on page 7 has been amended as shown below:

The following projection objective 2 25 can be constructed as a six-mirror projection objective. A wafer 14 is located on a carrier unit 13 as the object to be exposed.

The paragraph beginning at line 19 on page 7 has been amended as shown below:

As a result of the ability to adjust the mirror facets 6 and 8, different settings can be implemented in an exit pupil 15 of the lighting system which, at the same time, forms an entry pupil of the projection objective 2 25.

The paragraph beginning at line 1 on page 8 has been amended as shown below:

In figures 2 and 3, the beam path from the light source 1 via the reticle 12 as far as the entry exit pupil 15 is illustrated.